

## CORRECTION

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## Correction: Reliable high work-function molybdenum dioxide synthesis *via* template-effect-utilizing atomic layer deposition for next-generation electrode applications

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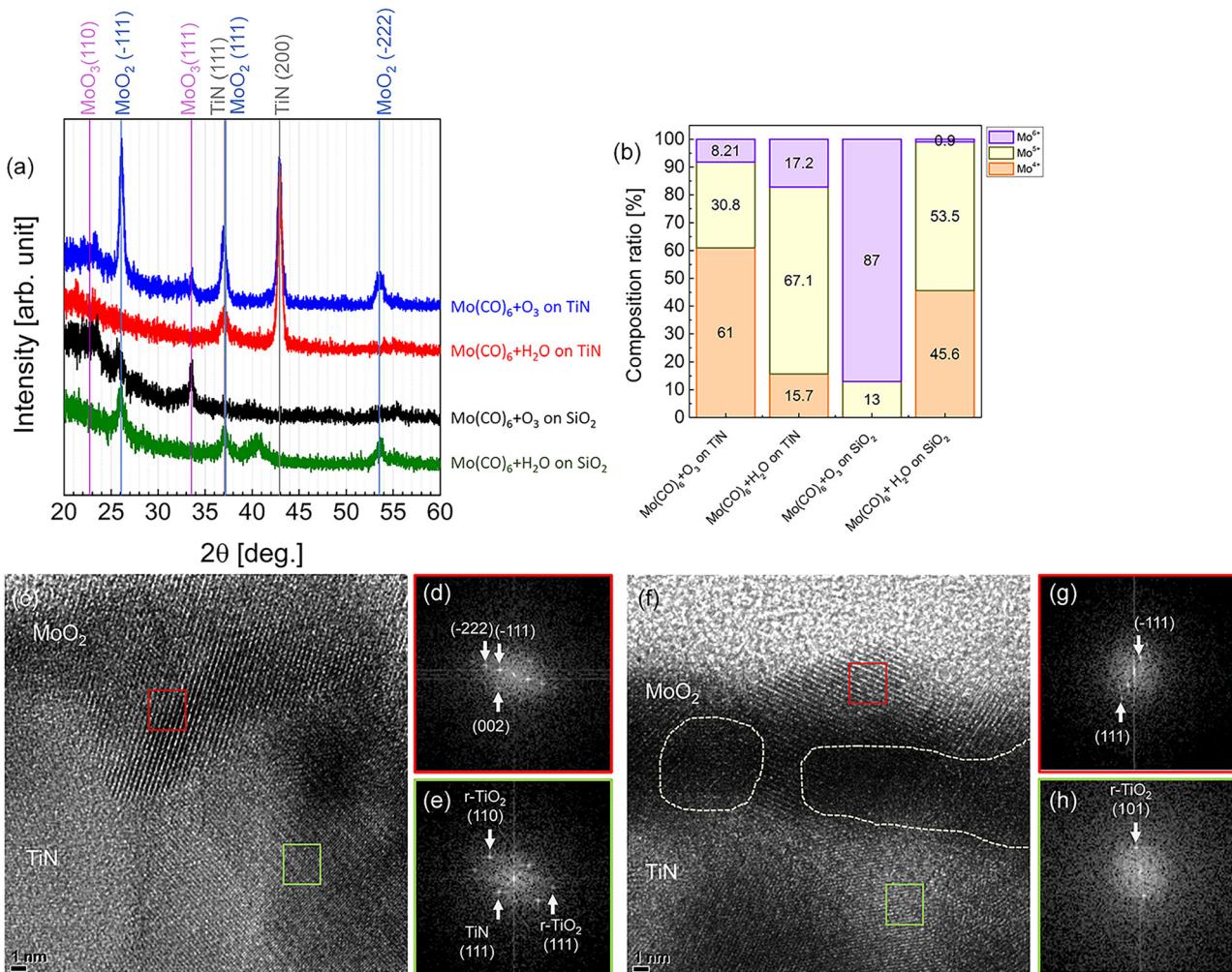
Correction for 'Reliable high work-function molybdenum dioxide synthesis *via* template-effect-utilizing atomic layer deposition for next-generation electrode applications' by Ye Won Kim *et al.*, *J. Mater. Chem. C*, 2022, <https://doi.org/10.1039/d2tc02104h>.

The authors regret that an incorrect version of Fig. 1(b) appeared in the published article. The corrected version of Fig. 1 and its caption are reproduced here.

The Royal Society of Chemistry apologises for these errors and any consequent inconvenience to authors and readers.

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**Fig. 1** (a) XRD patterns and (b) composition ratio of oxidation states of  $\text{MoO}_x$  thin films deposited under various conditions. (c) HR-TEM image of TiN/ $\text{MoO}_x$  deposited using  $\text{O}_3$  and FFT patterns of (d)  $\text{MoO}_2$  (indicated by red box in (c)) and (e) TiN surface (indicated by green box in (c)). (-111), (111), and (-222) in (d) indicate the planes of monoclinic phase  $\text{MoO}_2$ . r-TiO<sub>2</sub> in (e) indicates rutile-phased  $\text{TiO}_2$ . (f) HR-TEM image of TiN/ $\text{MoO}_x$  deposited using  $\text{H}_2\text{O}$ . The dashed line region indicates an amorphous area in the film. FFT patterns of (g)  $\text{MoO}_2$  (indicated by red box in (f)) and (h) the TiN surface (indicated by the green box in (f)).

